

Docket Number: 081468-0306399

Client Reference: P-0375.010-US

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Re Application of:

KURT et al.

Confirmation No. 8782

Application No. 10/686,813

Group Art Unit: 1756

Filed: October 17, 2003

Examiner: UNKNOWN

Title: LITHOGRAPHIC PROJECTION APPARATUS  
AND DEVICE MANUFACTURING METHOD

\* \* \* \*

**INFORMATION DISCLOSURE STATEMENT**

Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR 1.56, the attention of the Patent and Trademark Office is hereby directed to the reference listed on the attached PTO-1449. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed before the mailing date of the first Office Action on the merits in the present application. No certification or fee is required.

Respectfully Submitted,

PILLSBURY WINTHROP LLP

  
Jean-Paul G. Hoffman  
Registration Number 42663

Date: February 20, 2004

P.O. Box 10500  
McLean, VA 22102  
Telephone: (703) 905-2000  
Facsimile: (703) 905-2500



Atty.  
Dkt. No.

M#

Client Ref.

306399

P-0375.010-US

# **INFORMATION DISCLOSURE STATEMENT BY APPLICANT**

Applicant: KURT et al.

Appln. No.: 10/686,813

Filing Date: October 17, 2003

Date: February 20, 2004 Page

1

of 1

Examiner:

Group Art Unit: 1756

## **U.S. PATENT DOCUMENTS**

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	AR					
	BR					
	CR					
	DR					
	ER					
	FR					
	GR					
	HR					
	IR					
	JR					
	KR					
	LR					
	MR					

## **FOREIGN PATENT DOCUMENTS**

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclose	No
	NR							
	OR							
	PR							
	QR							
	RR							
	SR							
	TR							
	UR							
	VR							
	WR							

## **OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)**

	XR	SILVAST et al., "High-power plasma discharge source at 13.5 nm and 11.4 nm for EUV lithography," <i>Proc. SPIE</i> 3676:272-275 (1999)			
	YR				
	ZR				
	AAR				
	BBR				
	CCR				

Examiner

Date Considered:

\*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.